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**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

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In re application of: Wang et al.

Attorney Docket No.:  
NOVLP085/NVLS-2875

Application No.: NEW

Examiner: UNASSIGNED

Filed: HEREWITH

Group: UNASSIGNED

Title: PLASMA DETEMPLATING AND  
SILANOL CAPPING OF POROUS  
DIELECTRIC FILMS

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**INFORMATION DISCLOSURE STATEMENT**  
**37 CFR §§1.56 AND 1.97(b)**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

The references listed in the attached PTO Form 1449, copies of which are attached, may be material to examination of the above-identified patent application. Applicants submit these references in compliance with their duty of disclosure pursuant to 37 CFR §§1.56 and 1.97. The Examiner is requested to make these references of official record in this application.

This Information Disclosure Statement is not to be construed as a representation that a search has been made, that additional information material to the examination of this application does not exist, or that these references indeed constitute prior art.

This Information Disclosure Statement is: (i) filed within three (3) months of the filing date of the above-referenced application, (ii) believed to be filed before the mailing date of a first Office Action on the merits, or (iii) believed to be filed before the mailing of a first Office Action after the filing of a Request for Continued Examination under §1.114. Accordingly, it is believed that no fees are due in connection with the filing of this Information Disclosure Statement. However, if it is determined that any fees are due, the Commissioner is hereby authorized to charge such fees to Deposit Account 500388 (Order No. NOVLP085).

Respectfully submitted,  
BEYER WEAVER & THOMAS, LLP



Jeffrey K. Weaver  
Registration No. 31,314

<b>Form 1449 (Modified)</b>			
<b>Information Disclosure Statement By Applicant</b>			
(Use Several Sheets if Necessary)			
		Atty Docket No. NOVLP085/NVLS-002875	Application No.: Unassigned
		Applicant: Wang et al.	
		Filing Date HEREWITH	Group Unassigned

#### U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
	A1	6,329,017	12/11/01	Liu et al.			
	A2	6,383,466	5/7/02	Domansky et al.			
	A3	6,365,266	4/2/02	MacDougall et al.			
	A4	5,504,042	4/2/96	Cho et al.			
	A5	5,858,457	1/12/96	Brinker et al.			
	A6	6,270,846	8/7/01	Brinker et al.			
	A7	6,387,453	5/14/02	Brinker et al.			
	A8	6,420,441	10/10/99	Allen et al.			
	A9	6,271,273	10/10/00	You et al.			
	A10	4,885,262	12/5/89	Ting et al.			
	A11	5,686,054	11/11/97	Barthel et al.			
	A12	5,851,715	12/22/98	Barthel et al.			
	A13	6,140,252	10/31/00	Cho et al.			
	A14	6,392,017	5/21/02	Chandrashekhar			
	A15	6,386,466	5/14/02	Ozawa et al.			
	A16	4,357,451	11/2/82	McDaniel			
	A17	6,479,374	11/12/02	Ioka et al.			
	A18	6,548,113	4/15/03	Birnbaum et al.			

#### Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No
	B1							

#### Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication		
	C1	Liu et al., "Mesoporous Silica Film From a Solution Containing a Surfactant and Methods of Making Same," U.S. Patent Application Publication No. US2002/0034626, Published March 21, 2002, 27 Pages		
	C2	Wu et al., "Use of Multifunctional SI-Based Oligomer/Polymer for the Surface Modification of Nanoporous Silica Films," U.S. Patent Application Publication No. US2002/0001973, Published January 3, 2002, 13 Pages		
	C3	Cho et al., "Plasma Treatments of Molecularly Templatated Nanoporous Silica Films," Electrochemical and Solid-State Letters, 4 (4) G35-G38 (2001)		

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	Applicant: Wang et al.	
	Filing Date HEREWITH	Group Unassigned

C4	Justin F. Gaynor, "In-Situ Treatment of Low-K Films-With a Silylating Agent After Exposure To Oxidizing Environments," U.S. Patent Application No.10/056,926 filed January 24, 2002, 34 Pages
C5	Gangpadhyay et al., "The First International Surface Cleaning Workshop," Northeastern University, November 11-14, 2002
C6	Yung et al., "Spin-on Mesoporous Silica Films with Ultralow Dielectric Constants, Ordered Pore Structures, and Hydrophobic Surfaces," Adv. Mater. 2001, 13, No. 14, 1099-1102
C7	Schulberg et al., "System for Deposition of Mesoporous Materials," U.S. Patent Application No. 10/295,965, filed November 15, 2002, 64 Pages
C8	Watkins et al., "Mesoporous Materials and Methods," U.S. Patent Application No.10/301,013, filed November 21, 2002, 34 Pages
Examiner	Date Considered

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.